

## PATENT ABSTRACTS OF JAPAN

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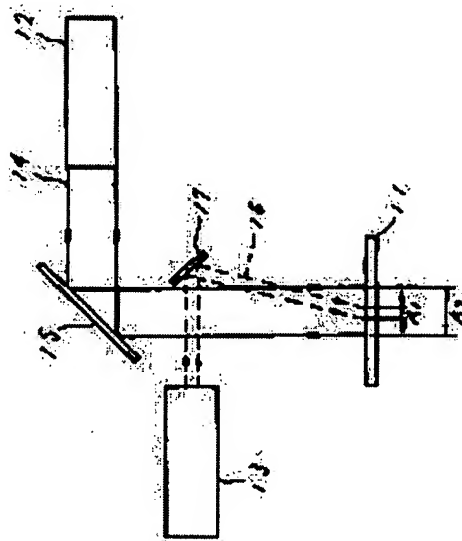
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### (54) LASER ANNEALING DEVICE

#### (57)Abstract:

**PURPOSE:** To allow the simultaneous heat treatment of different kind of substances, and suffice the output from individual laser light sources by a method wherein, using a plurality of laser light sources which generate laser lights with different wave lengths, a region larger than a required heating area is preheated by one laser light source, and thereafter a part of the preheated region is heated or fused by the other laser light source.

**CONSTITUTION:** First, the laser light 14 from the laser light source 12 is irradiated onto the region A2 via a mirror 15, and accordingly said region A2 is preheated to a suitable temperature less than the melting point thereof. Next, the laser light 16 from the laser light source 13 is irradiated onto the required treatment region A1 a part of the preheated region A2 via a mirror 17, and accordingly said region A1 is fused. Therefore, a required treatment region A is annealed without the necessity of enlarging so much the output of individual laser light sources 12 and 13. Besides, the annealing treatment can be performed to a large area at a time.



*Further, the heat treatment before and after the laser annealing can be simultaneously performed.*

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#### **LEGAL STATUS**

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